## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

PATENT APPLICATION

Inventor:

Yoshi Ono

Serial No.:

Not Yet Assigned

Attorney Docket No. SLA 0669

Filed:

Herewith

Title:

LOW TEMPERATURE

NITRIDATION OF SILICON

Honorable Commissioner for Patents Washington, D.C. 20231

## INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Sir:

Listed on attached Form PTO-1449 is information submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication is submitted herewith.

Applicant respectfully requests that the listed information be considered by the Examiner and made of record in the above-identified application.

Respectfully submitted.

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LIST OF PRIOR ART CITED				Application Number		
				Filing Date	06-23-03	
BY APPLICANT				First Named Inventor	Yoshi Ono	
				Group Art Unit		
(use as many sheets as necessary)			necessary)	Examiner Name		
Sheet	1	of	1	Attorney Docket No.	SLA.0669	

U.S. PATENT DOCUMENTS						
Examiner Cite No.¹		U.S. Patent Document Kind Number Code <sup>2</sup> (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear	
		6,274,510 B1	Wilk et al.	08-14-01		
1						

		FOREIG	N PATENT DOCUME	NTS		
	Cite No.1	Foreign Patent Dcument	Name of Patentee or Applicant	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant	T6
		Office <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup>	of Cited Document	MM-DD-YY	Passages or Figures Appear	
<del></del>						

OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T²		
		K. Watanabe et al., Controlling the concentration and position of nitrogen in ultrathin oxynitride films formed by using oxygen and nitrogen radicals, Appl. Phys. Lett. 76, 2940 (2000).			
		J. Joseph et al., A kinetics study of the electron cyclotron resonance plasma oxidation of silicon, J. Vac. Sci. Technol. B10, 611 (1992).			

Examiner	-	Date	
Signature		Considered	<u> </u>

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not

considered. Include copy of this form with next communication to applicant.

'Unique citation designation number. 'See attached Kinds of U.S. Patent Documents. 'Enter Office that issued the document, by the two letter code (WIPO Standard ST.3). 'For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 'Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.19 if possible. 'Applicant is to place a check mark here if English language Translation is attached